

SUPPLEMENTARY INFORMATION

## Effect of Post-Annealing on Plasma Etching of graphene-coated-copper

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### Supplementary information

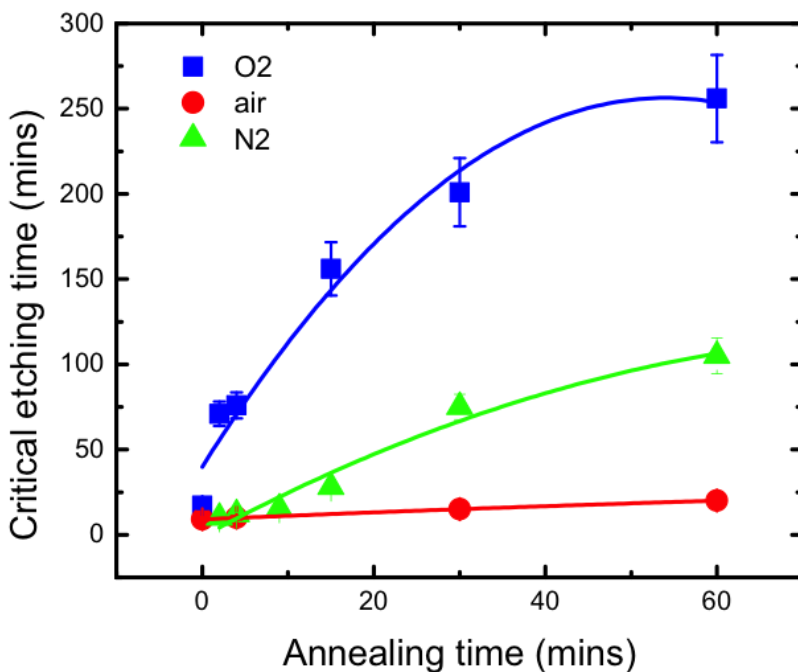


Figure 1 Critical etching times in mins for each process gas

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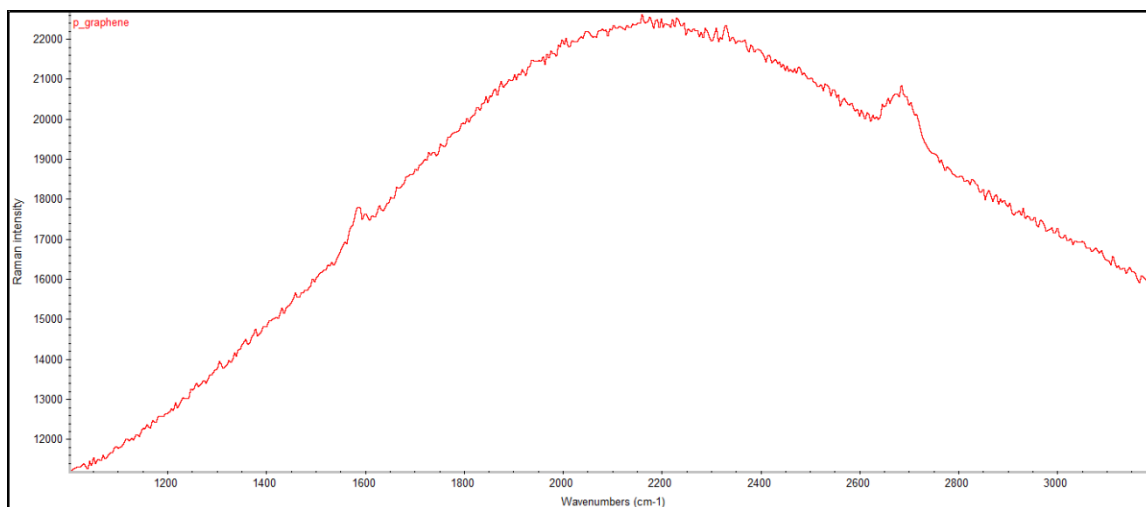


Figure 2a Raw Raman data for pristine graphene

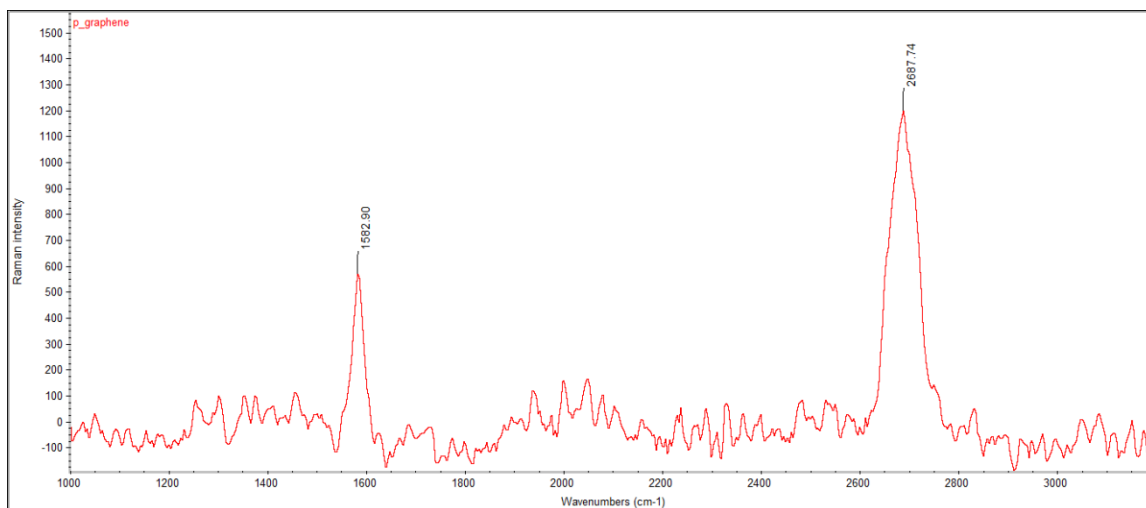


Figure 2b Raman data for pristine graphene after baseline correction of Cu